

POLOS® HOTPLATE 350

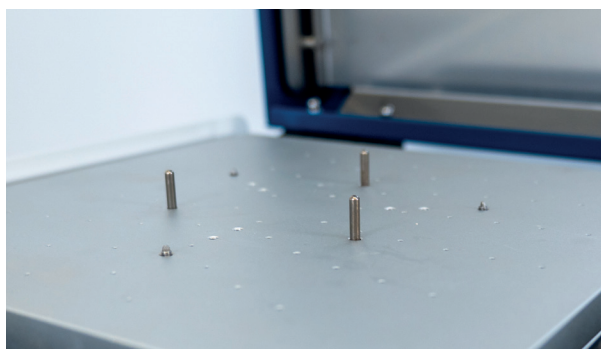
Our table-top hotplate is a versatile and affordable tool for R&D and pilot lines. It is designed with a soft-close lid and is suitable for soft bake as well as hard bake processes, and curing of photoresist, epoxy or any other work requiring precise temperature control. The POLOS® Hotplate 350 is available as an advanced version, which means it is standard equipped with complimentary features such as an N2 connector, lifting pins, vacuum bake, and proximity pins.



Also available with a
200 x 200 mm heating area!

HOTPLATE 350 ADVANCED

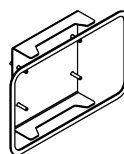
- Heater surface area 350 x 350 mm
- Suitable for 1 x 300 mm wafer
- Soft-close lid, enabling single-handed closing
- Glove-friendly operation
- Temperature range 50 - 230°C
- Programmable storage of 20 programs (Temperature/Time)
- Countdown timer (1 - 999 sec.)
- Temperature uniformity $\pm 1^\circ\text{C}$
- Equipped with programmable (electric) lifting pins set in radius to be defined
- Equipped with proximity pins to hold the wafer above the heating plate while baking
- Equipped with perforated vacuum plate to realize a hard contact bake
- Voltage: 230 or 110 VAC
- Heater block material: Aluminum (anodized)
- Housing material: Powder coated steel
- Including soft-close lid with N2 connection



Perforated vacuum plate and programmable lifting pins

EASILY CONVERTIBLE INTO AN INDECK MODEL

Using our specially designed indeck display bracket, you can easily convert the POLOS® hotplate into an indeck solution.



INDECK DISPLAY BRACKET



Glove-friendly operation

R26-1

SYSTEM DRAWINGS

